Docket No. 740819-442

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE In re Patent Application of Akihiko ISHIBASHI et al. Examiner: Savitri Mulpuri Serial No. 09/692,211 Filed: October 20, 2000 Group Art Unit: 2812 For: METHOD OF FABRICATING NITRIDE SEMI-Confirmation No.: 6705 CONDUCTOR DEVICE Certificate of Mailing I hereby certify that this correspondence is being deposited with the United States Postal Service with sufficient ay First Class Mail, in an envelope addressed to: Commissioner for Patents, Washington, DC 20231, on April 15, 2003. REQUEST FOR ACKNOWLEDGMENT OF INFORMATION DISCLOSURE STATEMENT

Sir:

Commissioner for Patents Washington, D.C. 20231

An Information Disclosure Statement with Form PTO-1449 was filed in the above-identified patent application on September 19, 2002. Applicants have received back from the Examiner a partially considered copy of the Form PTO-1449 initialed to acknowledge the fact that the Examiner has considered the cited disclosed information.

The Examiner is requested to initial and return to the undersigned a copy of the subject Form PTO-1449.

Should there be any questions concerning this communication, please telephone the undersigned at the number set forth below.

Respectfully submitted

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